



אוניברסיטת בן-גוריון בנגב
Ben-Gurion University
of the Negev

Nano-Fabrication
Center

Raith EBPB 5150 Electron Beam Lithography



Description

The EBPB is a high-performance electron beam lithography system with 50kV / 100 kV write modes and high-resolution lithography below 5 nm. The EBPB offers the unique combination of a powerful and stable beam with up to 350 nA beam current and fully automated calibration and alignment procedures. In conjunction with BEAMER software (GenISys GmbH), the system provides advanced fracturing capabilities and very short writing times.

Specifications / Capabilities

Wafer size : Up to 6" wafers

Maximum Field size: 1mm

Overlay accuracy: <30nm

Stitching accuracy : <15nm (Field size 250 μ m), <30nm (Maximum Field size)

Beam Current Up to: 350nA

Link

<https://www.raith.com>

<https://www.genisys-gmbh.com/>